

**HEIDELBERG**  
INSTRUMENTS



# μPG 101

TABLETOP MICRO PATTERN GENERATOR



50 μm SU-8, aspect ratio 10:1

# **μPG 101**

## Tabletop Micro Pattern Generator

The μPG 101 is an extremely economical and easy to use micro pattern generator for direct writing applications and low volume mask making. The system can be used for applications such as MEMS, Bio MEMS, Integrated Optics, Micro Fluidics or any other application that requires high precision, high-resolution microstructures. The μPG 101 offers a small footprint of only 60 x 75 cm<sup>2</sup>, featuring a compact design with all electronic components integrated into the system. A personal computer is used as system control. The GUI based control software makes it easy for users to convert the designs, perform a manual or automatic alignment and start the exposure.

The μPG 101 is designed to provide an easy and fast way to create the microstructures needed for your business or research. The tabletop system features exchangeable write modes to meet the resolution and write speed requirements of your specific application. It is the only available desktop lithography system in the market, which can produce sub-micron features. The small address grid allows placement of structures with very high accuracy. The real-time autofocus system monitors and corrects focus position during exposure, which guarantees high resolution and repeatability over the entire exposure area. Small address grid and real-time autofocus system are essential features for a professional micro pattern solution.

The standard system is equipped with a diode laser at 405 nm, which presents a reliable laser source with a long lifetime. This laser can be used to expose the standard photoresists that are used in lithography. Alternatively, the system can be equipped with a laser diode at 375 nm, making it possible to expose standard resists and UV resists such as SU-8. The system offers a raster-scan and vector exposure mode for high resolution 2D patterns and in addition it is also possible to create complex 3D structures in thick photoresist in a single pass.

To ensure the quality of the produced structures, the μPG 101 utilizes a fixed optical path, a high precision mechanical structure and an air-bearing stage driven by linear motors. During exposure the stage position is constantly monitored by a high-resolution linear encoder system.

The camera of the μPG 101 enables the user to perform position measurements on the substrate as well as manual alignment. The optional automatic alignment system provides tools for an advanced alignment to already existing structures on the substrate, making it possible to perform multi-layer overlay exposures with high accuracy.

### **Key Features and Options**

Substrates up to 6" x 6"

Structures down to 0.6 μm

Address grid down to 20 nm

Basic gray scale exposure mode

Real time auto focus system

Standard or UV diode laser source

Vector and raster exposure mode

Exchangeable write modes

Camera system for alignment

Multiple data input formats

### SPECIFICATIONS

WRITE MODE	I	II	III	IV
Minimum Structure Size [μm]	0.6	1	2.5	5
Write Speed [mm <sup>2</sup> /minute]	1	5	35	90
Address Grid [nm]	20	40	100	200
Edge Roughness [3σ,nm]	100	120	200	400
Line Width Uniformity [3σ,nm]	150	200	400	800
Alignment Measurement Accuracy [3σ,nm]	200	200	400	800